

# Resin Wafer-Electrodeionization for Flue Gas Carbon Dioxide Capture

DOE Program Announcement Number: DE-FOA-0000065

ARPA-E Award: DE-AR0000024



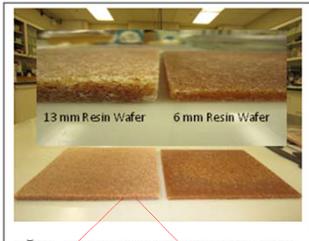
## Project Goals

- Develop Resin Wafer- Electrodeionization technology for CO<sub>2</sub> capture
- Target 90% CO<sub>2</sub> capture and release with 90% purity at COE target of less than 50%

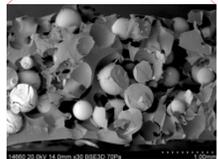
## Strategy

- Simultaneous CO<sub>2</sub> absorption & release
- Employ electrochemical pH control
- Decrease parasitic energy load

## Resin Wafer



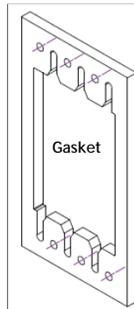
- Thickness: 6 and 13 mm in 11"x11"
- Porosity: 30% to 40%
- Ionic conductivity: 1.5 to 4.0 mS/cm
- Resin type: gel cationic and anionic
- Particle sizes: 50 μm to 400 μm



Scanning electron microscope image

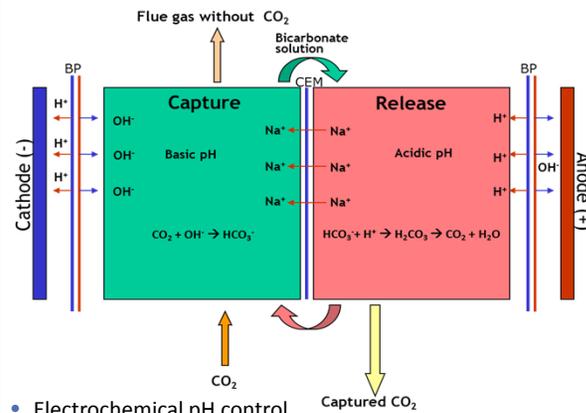


Resin wafer held within a gasket



Gasket

## Single Cell EDI



- Electrochemical pH control
  - Capture Cell – basic pH
  - Release Cell – acid pH
- Water splitting at bipolar membranes
  - Source of OH<sup>-</sup> for capture cells and H<sup>+</sup> for release cells
  - In-situ ion exchange regeneration
- Cationic-selective membranes
  - Na<sup>+</sup> ions migrate into capture cells after CO<sub>2</sub> release

## Flow Through Cell



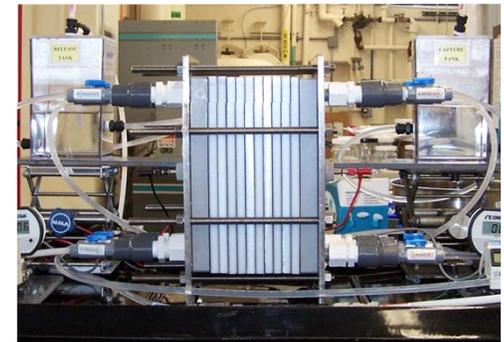
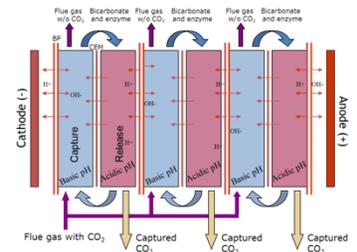
Gas and liquid flowing in a partial resin wafer held within a gasket



Gas and liquid flowing in a resin wafer held within a gasket

## CO<sub>2</sub>\_RW-EDI

Plate-and-frame module with alternating cationic-selective and bipolar ion exchange membranes between resin wafers



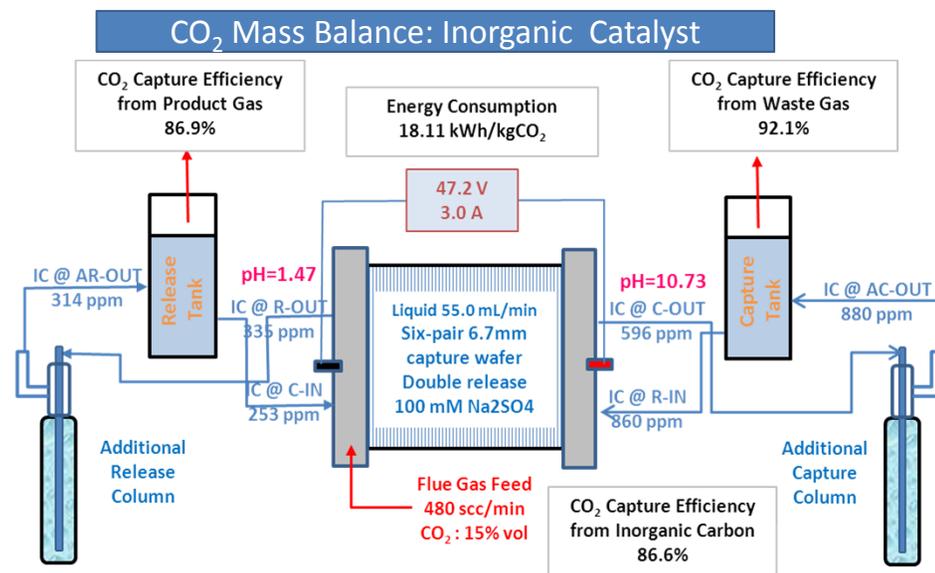
## Gas Analyzers



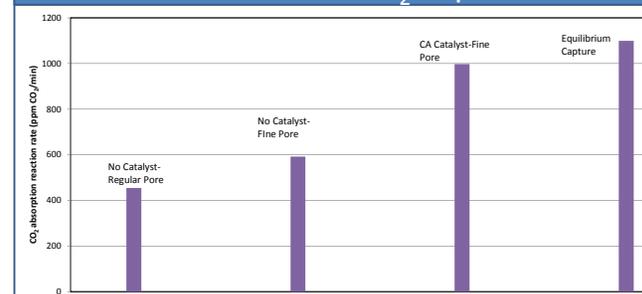
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## Effect of Pore Size on CO<sub>2</sub> Capture Rates



## Conclusion

- The process achieved 90% CO<sub>2</sub> capture at 90% purity and exceeded the energy consumption target.

## Summary of Improvements

System	G/L Ratio	Gas Flow Rate scc/min	% Capture	Electrical Power kWh/Kg CO <sub>2</sub>
Baseline Wafers	3	240	53	57
Enzyme Immobilized Wafers	5	300	58	16
Inorganic Catalyst	3	240	81	32
Inorganic Catalyst + Absorption Column	5	480	94	20
Inorganic Catalyst + Absorption Column + Better Gas Distribution	15	1000	46	9
Inorganic catalyst + Absorption Column + Release Column+ Better Gas distribution	9	480	92	18

## Acknowledgements

### Project Team



#### Nalco

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- Rebecca Stiles
- Lisa Wesoloski
- Robert Dorner
- Deepak Musale
- Wayne Carlson
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#### Argonne National Lab

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